The usage of resonance optical absorption method for measurement of Cu atoms during the plasma sputtering deposition

H Naghshara, S Sobhanian and N Sadeghi
1. Physics Department of Tabriz University, IRAN
2. Laboratoire de Spectrometrie Physique, Universite Joseph Fourier-Grenoble, FRANCE
E-mail: naghshara@yahoo.com

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Abstract
In this paper, the resonance optical absorption method, is used to measure the Cu atoms number density in different power levels of power supply. Atoms are sputtered from a Cu target during plasma magnetron sputtering deposition. For the light source, a commercial Cu hollow cathode lamp is used. For measurement of gas temperature, a small percentage of N₂ is added to the gas mixture and the gas temperature is found by optical emission technique.

Keywords: resonance optical absorption, plasma sputtering

For full article, refer to the Persian section.